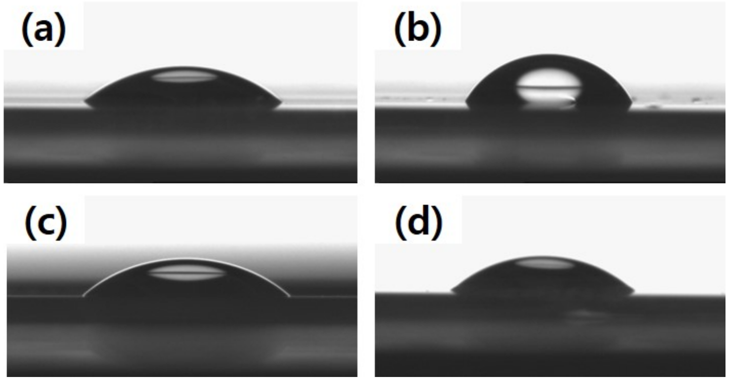
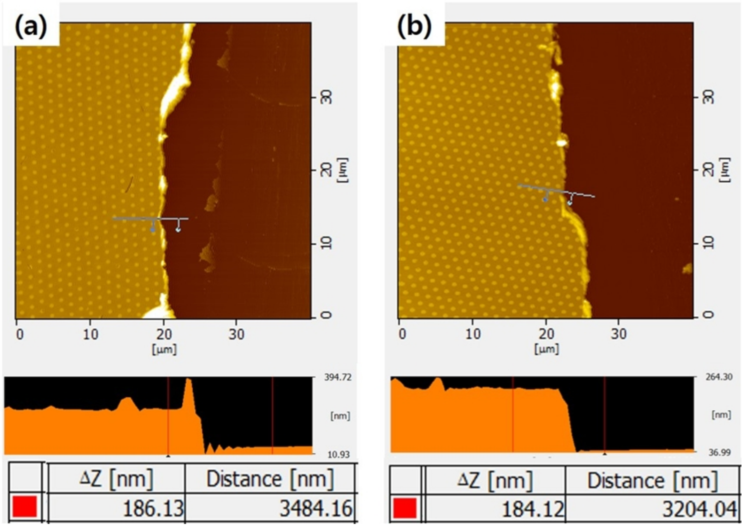


Fig. S1 Water contact angle of (a) bare SiOx substrate(40.4°), (b) SiOx substrate after printing with a flat PDMS mold during 10min at 130°C(62.3°), (c) SiOx substrate after printing with air plasma-treated PDMS mold during 10min at 130°C(41°) and (d) SiOx substrate after printing with air plasma-treated PDMS mold during 10min at room temperature(42°).



	ΔZ [nm]	Distance [nm]
🟥	186.13	3484.16

	ΔZ [nm]	Distance [nm]
🟥	184.12	3204.04

Fig. S2 The AFM images which reveal the thickness of residue layers of patterned photoactive layer prepared by (a) Thermal-assisted and (b) solvent-assisted soft nanoimprinting lithography on the PEDOT:PSS layer(30nm).

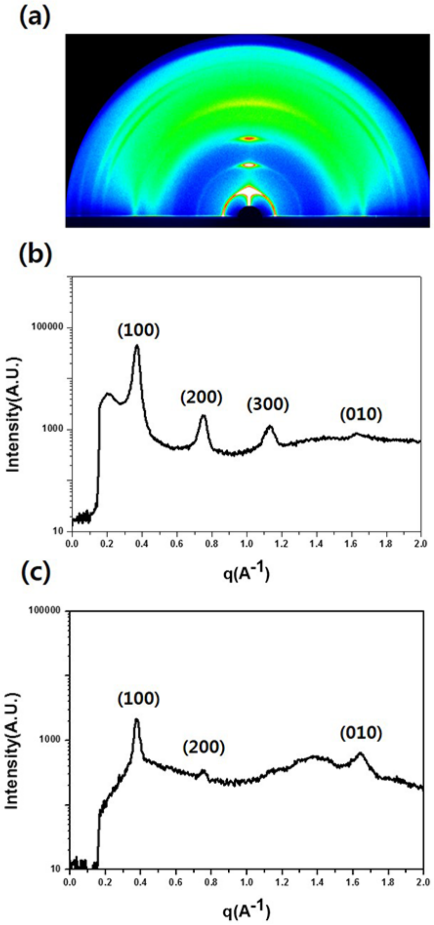


Fig. S3 Wide-angle GIXRD spectra of P3HT/PCBM photoactive layer films on the PEDOT:PSS coated ITO substrate. 2D image of (a) nanopatterned photoactive layer by the successive solvent-assisted SNL and thermal annealing in the presence of PDMS mold. 1D plot of (b) out-of-plane and (c) in-plane diffraction.